

This objective lens can be used for laser machining using pulsed laser of THG (355nm) YAG laser. Chromatic aberration is suppressed in both the visible and UV laser wavelength, achieving a high transmittance.

- With its long working distance and field curvature corrected, its natural observation image is obtained to the periphery of the visual field.
- With its long working infinity correction function; this objective lens can be used for a laser system and coaxial observation.
- It is also used for the observation of near ultra-violet light.
- This objective lens can be used with a pulse laser of visible light (532nm).
- Laser Damage Threshold (Typical) 0.05J/cm² (355nm), 0.1J/cm² (532nm)

(Laser pulse width 10ns, repetition frequency 20Hz)



## Guide

- Available fixed objective lens holder (LHO-26). WEB Reference Catalog Code W4024
- ▶ When the objective lens is fixed to a 2 axis holder, please consult our
- For laser processing, we offer a dichoric block (DIMC) and for laser unit with coaxial illumination and observation (OUCI-2).

ce Catalog Code W2041

## Attention

- When an objective lens is used in laser processing, use the diameter of the incident beam to extend to a size of half the pupil diameter (1/e²). A small light spot cannot be achieved when the incident beam is too narrow. Please note if there is a laser energy density increase, there will be a high possibility of damage to the objective lens.
- The surface of an objective lens can be contaminated by debris during processing. To avoid this, please have sufficient working distance (WD) and insert a thin protective glass on the objective.

  Magnification is the value when using the imaging lens f=200mm.
  - When used in a microscope lens barrel from other manufacturers there may be different magnifications. The actual magnification should be calculated from the ratio of the focal length of the objective lens and the focal length of the imaging lens to verify the focal length of the imaging lens barrel to be used.

**Outline Drawing** PAL-20-NUV-A PAL-50-NUV-A PAL-50-NUV-HR-L .706) (M26 P0.706) P0.706) 081) (M26 P0.70 W26 (ISO 8 W26 (ISO 17.25 (Working Distance) 15.1 (Working Distance) 10 (Working Distance) M26 W26  $\phi$ 33  $\phi$ 33 ₽3<del>3</del> **p**34 77.75 79.9 95 (Parfocal Length) 95 (Parfocal Length) 95 (Parfocal Length) PAL-100-NUV-HR PAL-100-NUV-A Typical Transmittance Data T: Transmission (M26 P0.706) W26 (ISO 8038) 100 3 Po.706) 90 (ISO 10 (Working Distance) 80 11.23(Working Distance) (M26 W26 70 60 φ33 φ34 [%] 50 PAL-20-NUV-A 40 PAL-50-NUV-A PAL-50-NUV-HR-I 30 83.77 PAL-100-NUV-A 20 PAL-100-NUV-HR 95 (Parfocal Length) 95 (Parfocal Length 10

Specifications										
Part Number	Item name	Magnifi- cation	Focal length f [mm]	Numerical aperture NA	Working distance WD [mm]	Resolution (λ=550nm) [μm]	Focal depth (λ=550nm) [μm]	Real f (Eyepiece \$\phi 24mm) [mm]	ield of view (Imaging device 1/2-inch) [mm]	Weight [kg]
PAL-20-NUV-A	MPlanApo NUV 20x	20x	10	0.40	17.25	0.69	±1.7	φ1.2	0.24×0.32	0.35
PAL-50-NUV-A	MPlanApo NUV 50x	50x	4	0.45	15.1	0.61	±1.4	φ0.48	0.10×0.13	0.36
PAL-50-NUV-HR-L	MPlanApo NUV HR 50x	50x	4	0.65	10.0	0.42	±0.65	φ0.48	0.10×0.13	0.51
PAL-100-NUV-A	MPlanApo NUV 100x	100x	2	0.57	11.23	0.48	±0.8	φ0.24	0.05×0.06	0.38
PAL-100-NUV-HR	MPlanApo NUV HR 100x	100x	2	0.70	10.0	0.39	±0.6	φ0.24	0.05×0.06	0.53

300

400

500

600

 $\lambda$  [nm]

700

800

Compatible Optic Mounts

I HO-26

Application Systems

Optics & Optical Coatings

> Opto-Mechanics

Bases

Manual Stages

**Actuators & Adjusters** 

Motoeized Stages

**Light Sources &** Laser Safety

Index

Guide

Mirrors

Beamsplitters **Polarizers** 

Lenses

**Filters** 

**Prisms** 

Substrates/Windows

Ontical Data

Maintenance

Selection Guide

**Achromats** 

**Focusing Lenses** 

fe Lenses **Objectives** 

**Expanders** 

**Others**